

JUN 04 2004

TRANSMITTAL OF FORMAL DRAWINGS

Docket No.

SLA0636

In Re Application Of: Katsuji Iguchi, Sheng Teng Hsu, Yoshi Ono & Jer-shen Maa

Serial No.	Filing Date	Batch No.	Examiner	Art Unit
10/035,503	10/25/2001		Alexander G. Ghyka	2812

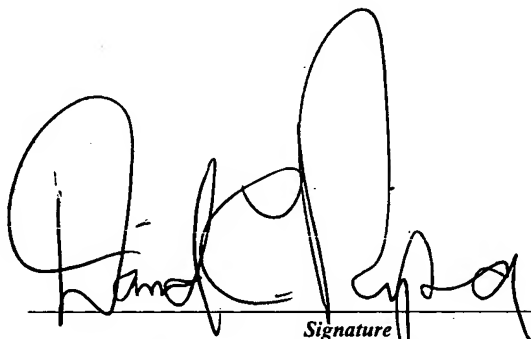
Invention: Method of Fabricating Deep-Sub-Micron CMOS Source/Drain with MDD and Selective CVD Silicide

Address to:
Assistant Commissioner for Patents
Washington, D.C. 20231

Transmitted herewith are:

4 sheets of formal drawing(s) for this application.

Each sheet of drawing indicates the identifying indicia suggested in 37 CFR Section 1.84(c)
on the reverse side of the drawing.



Signature

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Dated: June 2, 2004

I certify that this document and attached formal drawings
are being deposited on June 2 2004 with the
U.S. Postal Service as first class mail under 37 C.F.R. 1.8
and addressed to the Assistant Commissioner for Patents,
Washington, D.C. 20231.

Signature of Person Mailing Correspondence

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